

IN THE CLAIMS:

1. (Currently Amended) Process for preparing trichlorosilane by reacting silicon with silicon tetrachloride, hydrogen and optionally hydrogen chloride using catalysts, characterized ~~in that~~ wherein silicon is intensively mixed with the catalyst before the reaction ~~and wherein the mixing of silicon and catalyst takes place in the presence of at least one of hydrogen and gases~~ which have a reducing action.

2. (Original) Process according to claim 1, characterized in that the mixing of the silicon with the catalyst takes place in a mixer with rotating mixing tools.

3. (Previously Presented) Process according to Claim 1, characterized in that the mixing time is 1 to 60 minutes, preferably 5 to 20 minutes.

4. (Previously Presented) Process according to Claim 1, characterized in that the catalyst used is a copper catalyst or an iron catalyst.

5. (Original) Process according to Claim 4, characterized in that the catalyst used is a copper oxide catalyst or an iron oxide catalyst.

6. (Previously Presented) Process according to Claim 1, characterized in that the mixing of silicon and catalyst takes place at a temperature of from 100 to 400°C, preferably at 130 to

350°C.

7. (Previously Presented) Process according to Claim 1, characterized in that the mixing of silicon and catalyst takes place in the presence of hydrogen.

8. (Previously Presented) Process according to Claim 1, characterized in that the reaction is carried out at a pressure of from 1 to 40 bar (absolute).

9. (Previously Presented) Process according to Claim 1, characterized in that the reaction is carried out at temperatures of from 400 to 800°C.

10. (Previously Presented) Process of preparing silane and/or ultrapure silicon, characterized in that the starting material is trichlorosilane obtained according to Claim 1.

11. (New) A process for preparing trichlorosilane, the process comprising the steps of:

mixing silicon with a catalyst in a presence of a gas having a reducing action to form a silicon catalyst mixture;

5 reacting said silicon catalyst mixture with silicon tetrachloride and hydrogen to form trichlorosilane.

12. (New) A process in accordance with claim 11, wherein:

said mixing is performed to block formation of an oxide layer on the silicon.

13. (New) A process in accordance with claim 11, wherein:

said mixing is performed to have the catalyst adhere to a surface of the silicon.

14. (New) A process in accordance with claim 11, wherein:

said gas having the reducing action includes one of hydrogen and carbon monoxide.

15. (New) A process in accordance with claim 11, wherein:

said mixing is performed in a temperature range of 100 - 400 degrees C.

16. (New) A process for preparing trichlorosilane, the process comprising the steps of:

mixing silicon with a catalyst to have the catalyst adhere to a surface of the silicon and to form a silicon catalyst mixture;

5 reacting said silicon catalyst mixture with silicon tetrachloride and hydrogen to form trichlorosilane.

17. (New) A process in accordance with claim 16, wherein:

said mixing is performed to comminute the catalyst.

18. (New) A process in accordance with claim 16, wherein:

said mixing is performed in a presence of an inert gas.

19. (New) A process in accordance with claim 16, wherein:

said mixing is performed at a temperature high enough to remove moisture residues from said silicon catalyst mixture and increase adhesion of the catalyst to the silicon.

20. (New) A process in accordance with claim 16, wherein:

said reacting is performed in a fluidized bed.